

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A chemical amplifying type positive resist composition comprising

a resin which has a polymerization unit derived from hydroxystyrene and a polymerization unit derived from 2-ethyl-2-adamantyl (meth)acrylate, and is insoluble or poorly soluble itself in an alkali, but becomes alkali-soluble after dissociation of the above-mentioned acid unstable group by the action of an acid;

a radiation sensitive acid generating agent comprising a sulfonium salt; and

polypropylene glycol.

2. (Original) The chemical amplifying type positive resist composition according to claim 1, wherein content of the propylene glycol is from 0.1 to 5% by weight of the total solid content in the resist.

3. (Original) The chemical amplifying type positive resist composition according to claim 1, wherein weight-average molecular weight of the polypropylene glycol is from 500 to 5000.

4. (Original) The chemical amplifying type positive resist composition according to claim 1, wherein the radiation sensitive acid generating agent contains at least one compound selected from the group consisting of onium salt compounds, organo-halogen compound, sulfone compounds, sulfonate compounds, and the like.

5. (Previously Presented) The chemical amplifying type positive resist composition according to claim 2, wherein weight-average molecular weight of the polypropylene glycol is from 500 to 5000.

6. (Previously Presented) The chemical amplifying type positive resist composition according to claim 5, wherein the radiation sensitive acid generating agent contains at least one compound selected from the group consisting of onium salt compounds, organo-halogen compound, sulfone compounds, sulfonate compounds, and the like.

7. (New) The chemical amplifying type positive resist composition according to claim 1, wherein the sulfonium salt is triphenylsulfonium 2,4,6-triisopropylbenzenesulfonate.